

NanolC

Accelerating beyond-2nm chip innovation across Europe

Inge Asselberghs, imec





NanolC will provide Europe with a **beyond-2nm** leading edge system-on-chip pilot line.

It will develop advanced **logic**, novel **memories** and advanced **interconnect** technologies. Infrastructure &
EquipmentTechnology
developmentAccess &
selectionEducation & work
force
development





Meet the consortium

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- Project coordinator
- New cleanroom facility
- Advance logic, memory and interconnect technologies coordinator

Flanders State of the Art



- 2D materials and other deposited semiconductors for eDRAM (lab \rightarrow fab)



- Next generation CFETs
- 2D materials for eDRAM
- Device and design using SOT-MRAM





 Design and characterization of macros for analog and RF

- IC packaging, reliability and failure analysis
- Thermal and stress characterization



- Support processing and characterization by (cryo-) TEM-SEM-ZC-EDX
- Exploratory research by IR-AFM, SHG





NanolC activities within imec's pilot line







Future HPC system concept leveraging NanolC technologies





Technology platforms in NanolC scope:



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Advanced logic: nanosheet FET

- Functional CMOS demonstrated
- Test Vehicle \rightarrow ready for further process and module exploration w material and tool suppliers
- Electrical result → N2 research PDK



H. Arimura et.al. IEEE VLSI, 2024





Embedded memory macro for cache applications

SOT-MRAM

SOT-MRAM will be integrated on **40nm CMOS** technology





Latest results show excellent read/write and retention (>10 yrs) properties

eDRAM

Latest results show excellent retention achieved on side-by-side 2T0C*



Capacitorless eDRAM is now considered one the most promising candidates for Al applications

• **Upcoming:** availability of SOT eMRAM PDK and eDRAM PDK





Advanced interconnect: towards platform for prototyping

D2W Hybrid bonding

Flow option down selected: Ist electrical yield at 2um pitch



Fine pitch RDL Enablement 1.3um metal width interconnect



1.3 µm L/S lithography



1.3 μm L/S after CMP





To enable early exploration of developed technologies, NanoIC offers:



SYSTEM EXPLORATION PDKs

available to industry (including SMEs and start-ups) and academia





N2 PDK – Pathfinding PDK for future logic devices An explorative design environment for 2nm Gate All Around (GAA) Transistors

The NanolC project provides a comprehensive PDK environment for

designing,

- experimenting with, and
- testing innovative IC solutions on advanced nodes.



The PDKs are continuously benchmarked

with physical devices (fabricated in imec's cleanrooms),

for maximum adherence to **realistic electrical behavior** of devices.







To build a skilled European semiconductor workforce, the NanoIC pilot line offers:





INTERNSHIPS

PHDs

PDK WORKSHOPS



EXPERT COURSES











N2 PATHFINDING PDK: ADVANCED PDK WORKSHOP

24-25 June, IMEC Leuven, Belgium





N2 PDK – Hands-on training

Extensive N2 PDK training to engage directly with our R&D Team Next session: 24-25 June 2025

Day I: Introduction to N2 Node and Open PDK:

- Process Integration,
- Standard Cell,
- Back-side Power Delivery Networks
- and more.

Day 2: Hands-On EDA Tool Application











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Coordinated by

The acquisition and operation of the NanolC pilot line are jointly funded by the Chips Joint Undertaking, through the European Union's Digital Europe (101183266) and Horizon Europe programs (101183277), as well as by the participating states Belgium (Flanders), France, Germany, Finland, Ireland and Romania.

Funded by the European Union.Views and opinions expressed are however those of the author(s) only and do not necessarily reflect those of the European Union or Chips Joint Undertaking. Neither the European Union nor the granting authority can be held responsible for them.

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Pilot line project partners













